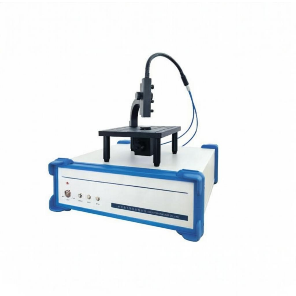
NWH3000 Film Thickness Tester

Description

The NWH3000 film thickness tester is a high-precision instrument that measures film thickness using spectral reflection technology. Its measurement range covers from nanometers to micrometers, enabling precise measurement of film thickness for substances such as photoresists, oxides, silicon or other semiconductor films, organic films, and conductive transparent films. It is widely used in the fields of semiconductors, microelectronics, and biomedicine.



Application

- Photovoltaic film thickness analysis
- Semiconductor films (photomask resists, process films, dielectric materials)
- Liquid crystal display (OLED, glass thickness, ITO)
- Optical coating (hard coating thickness, anti-reflection coating)
- High molecular films (PI, PC)
- Metal material film thickness

Features

- High precision
- Non-contact measurement
- Wide material compatibility
- Rapid measurement
- Simple operation
- High adaptability

Technical Specifications

Spectral Wavelength Range	200~1700 nm (Optional)

Thickness Measurement Range	5nm~250um
Measurement of n&k Thickness	≥50 nm
Accuracy	2nm or 0.2% (whichever is greater)
Repeatability	0.1nm
Spot Size	Small to 0.5mm
Sample Size	Diameter from 50mm to 300mm or larger